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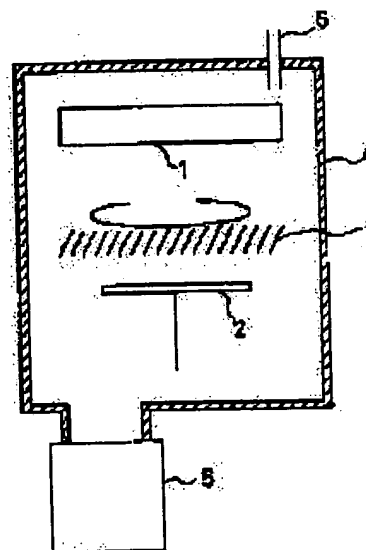
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## (54) THIN FILM DEPOSITION SYSTEM

### (57)Abstract:

**PURPOSE:** To improve the reliability of products by installing a slit vertically inclined from a substrate between the substrate and a target and turning the substrate and/or slit to form a uniform film inside micropores on the substrate.

**CONSTITUTION:** This system consists of a target 1, a slit 3, a device for turning the substrate 2 and/or slit 3, etc. The target 1 is formed with a raw material for a thin film and installed in the place opposite to the substrate 2. The slit 3 is installed between the substrate 2 and the target 1 and sputter atoms in the inclined direction are passed through the slit. The sputtering atoms having an incident angle equal to the inclined angle of the slit 3 are passed through the slit 3 to reach the substrate 2, and further, since the sputter atoms reach the whole area of the side of the micropores by turning the substrate 2 and/or slit 3, a uniform film is formed inside the micropores.



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